Characterization of AZO thin films grown on various substrates by using facing target sputtering system

이창현¹, 손선영², 배 장³, 이창규¹, 김화민⁴*

¹대구가톨릭대학교 전자전기공학과, ²포항공과대학교 창의IT융합공학과, ³(주)미주테크, ⁴대구가톨릭대학교 신소재화학공학과

Al doped ZnO(AZO) films as a transparent conductive oxide (TCO) electrode were deposited on glass, polyethylene naphthalate (PEN) and polyethylene terephthalate (PET) at room temperature by a conventional rf-magnetron sputtering (CMS) and a facing target sputtering (FTS) using Al2O3 and ZnO targets. In order to investigation of AZO properties, the structural, surface morphology, electrical, and optical characteristics of AZO films were respectively analyzed. The resistivities of AZO films using FTS system were 6.50×10⁻⁴ Ωcm on glass, 7.0×10⁻⁴ Ωcm on PEN, and 7.4×10⁻⁴ Ωcm on PET substrates, while the values of AZO films using CMS system were 7.6×10⁻⁴ Ωcm on glass, 1.20×10⁻³ Ωcm on PEN, and 1.58×10⁻³ Ωcm on PET substrates. The AZO-films deposited by FTS system showed uniform surface compared to those of the films by CMS system. We thought that the films deposited by FTS system had low stress due to bombardment of high energetic particles during CMS process, resulted in enhanced electrical conductivity and crystalline quality by highly c-axis preferred orientation and closely packed nano-crystalline of AZO films using FTS system.

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